

Understanding Warpage Behavior on Different Handling Platforms of FOWLP

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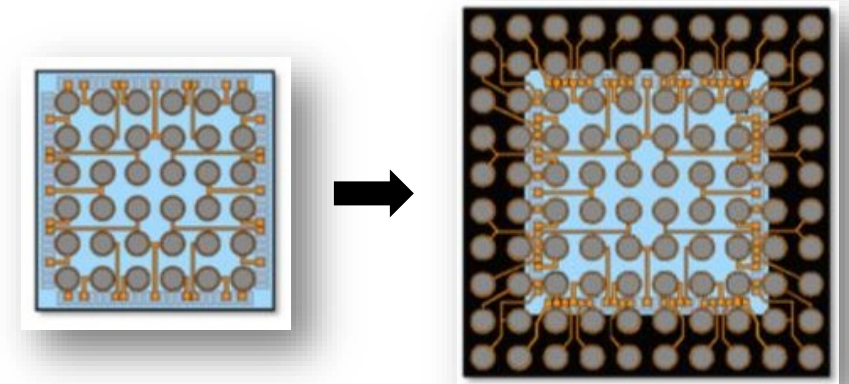


Contents of the Presentation

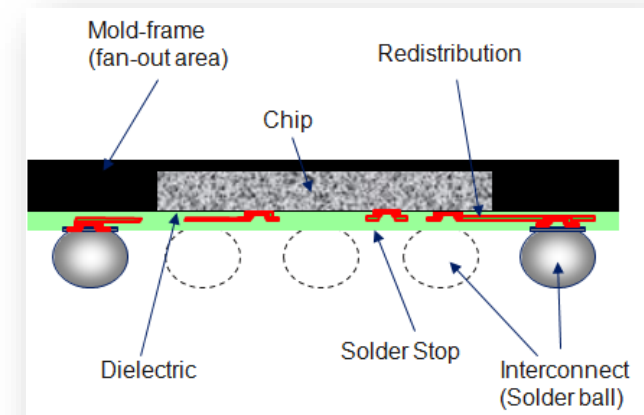
- What is Fanout
- Warpage in Fanout
- Issues in the Production
- Test Set-up and Result
- Conclusion

What is Fanout

- **Fan-out** is a type of advanced chip packaging where the redistribution layer (RDL) are routed outside the surface area of the die.
- Several noted advantages are:
 - Good electrical performance
 - Enables high density routing
 - Enables multi die package configuration

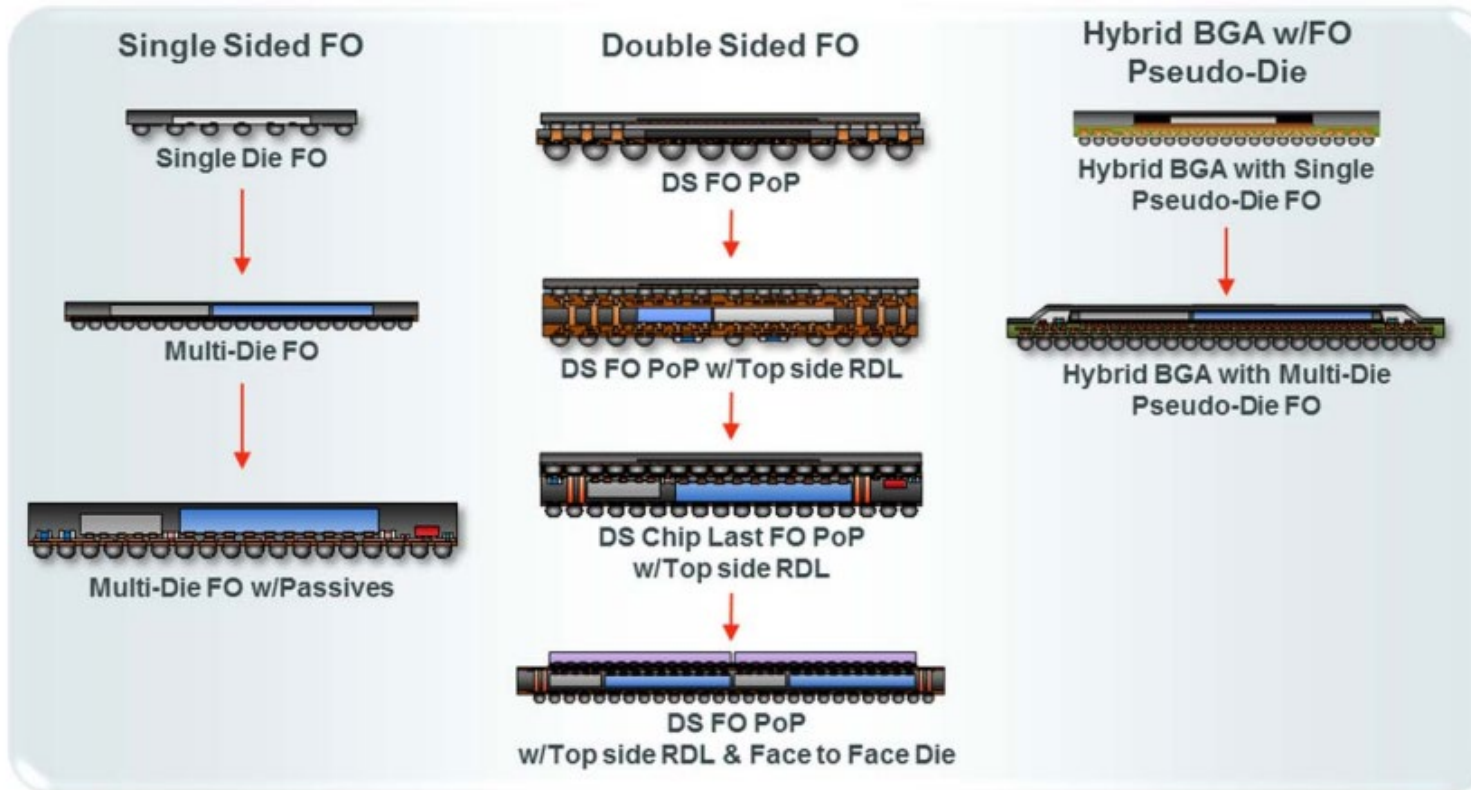


Credits: ASE



Credits: Infineon

What is Fanout



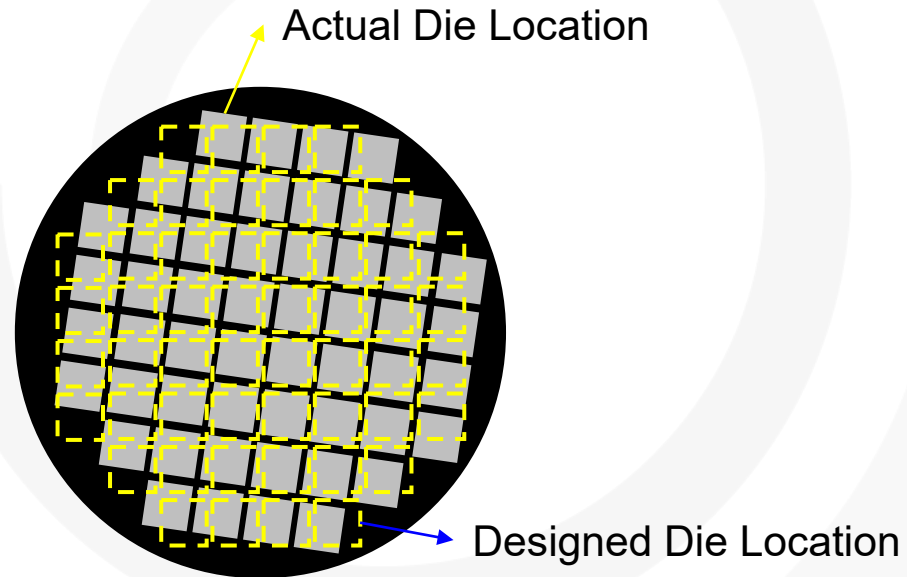
Credits: HR Annual Symposium 2020

As the complexity increases newer challenges are being encountered.

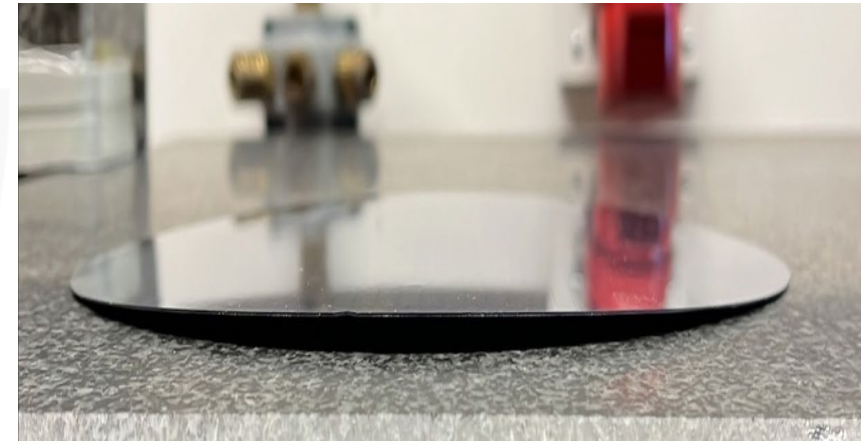
- Finer line and space features in RDL formation
- 3D through-mold connectivity
- Incorporation of passive components into the fan-out structure
- Die placement speed and accuracy
- Mold compound development
- Thinner fan out packages

What is Fanout

FOWLP, FOPLP

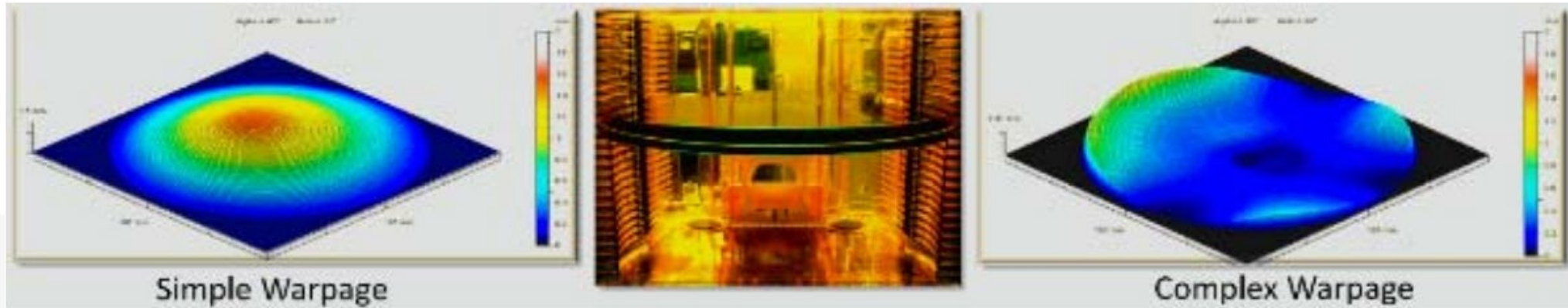


Die Shift is a defect in which the actual die location has an offset from the pre-defined position by a certain distance.



Warpage is the physical deformation encountered by the wafer due to coefficient of thermal expansion (CTE) mismatch between silicon and mold

Warpage in Fanout



Credits: HRAAnnual Symposium 2021; J. Hunt ASE

Process and Yield Impact

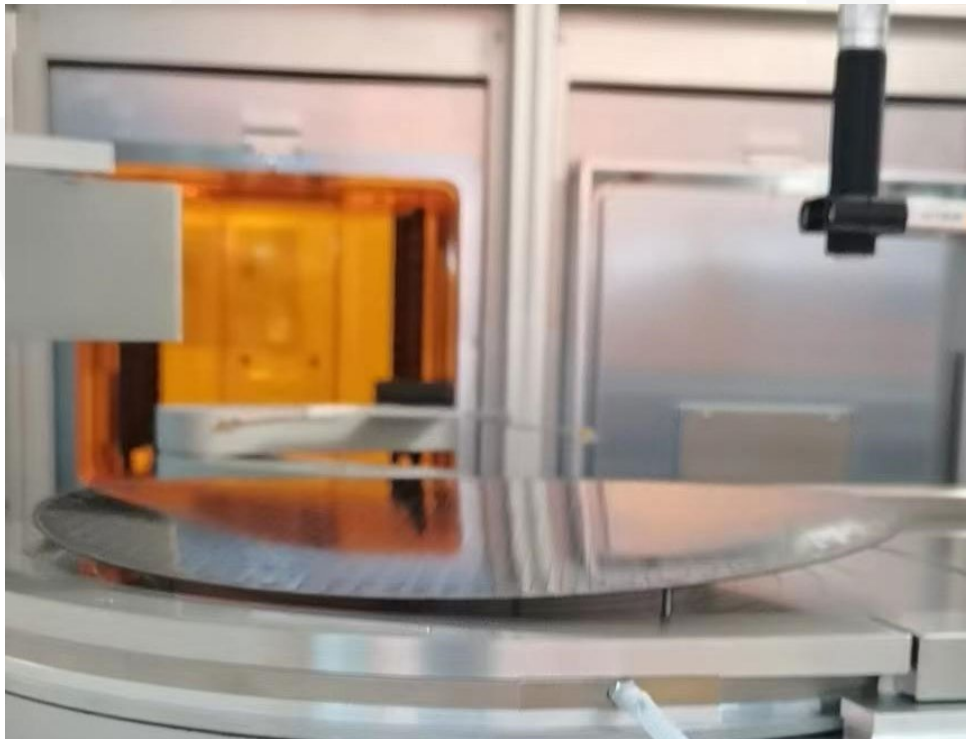
- Via Formation
- RDL and UBM Formation
- Soldering and Balling
- Package Singulation

Production and Equipment Impact

- Production Downtime
- Equipment Excursion
- Frequent Handling Design Changes

Issues in the Production

Production and Equipment Impact

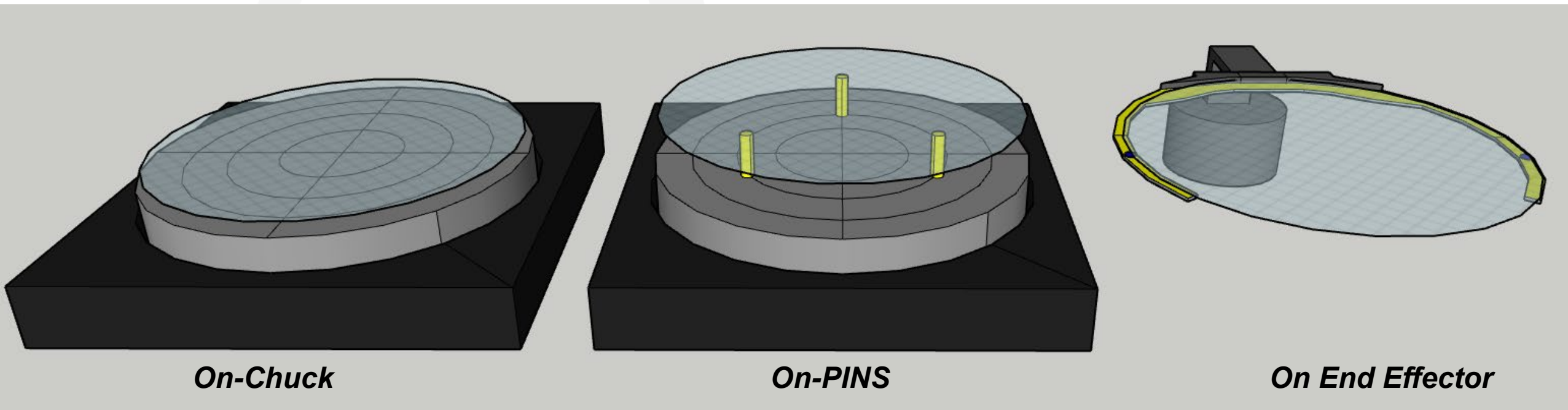


- Frequent machine alarm requiring operator intervention
 - Vacuum failure on chuck
 - Robot handling failure
 - Wafer alignment failure
 - Wafer sagging on pins

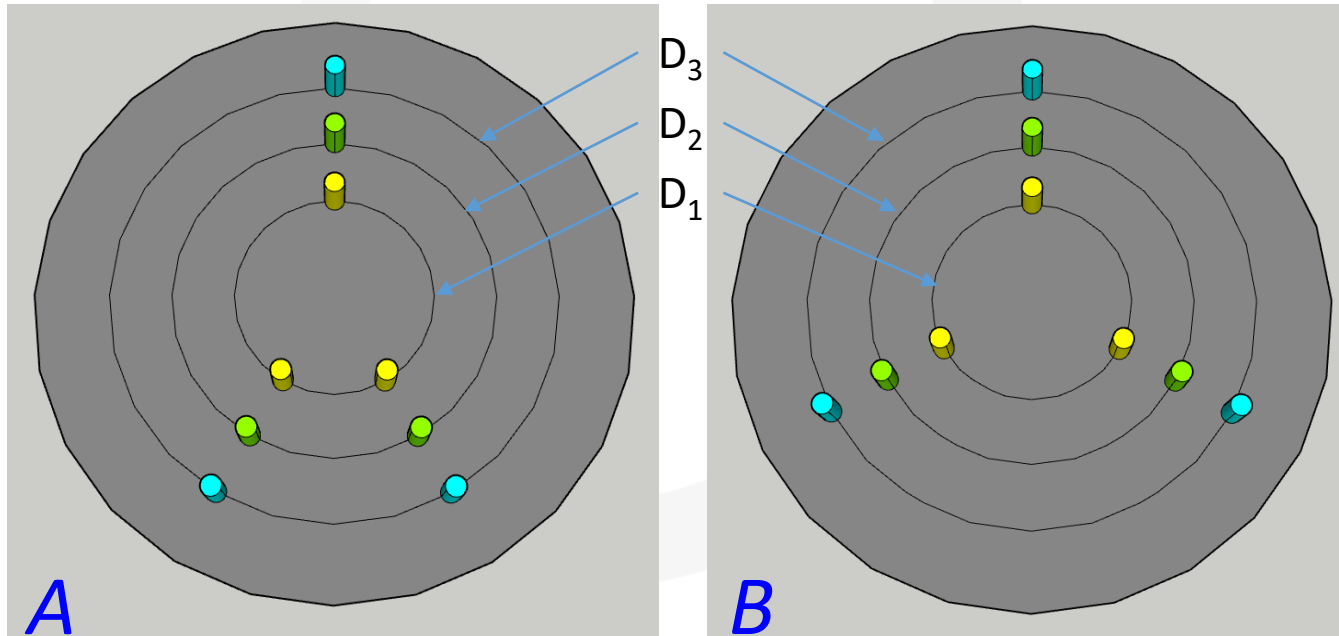


Test Set-up and Motivation

Understand how the warp wafers behave in different design of pins as well as end-effector suctions.



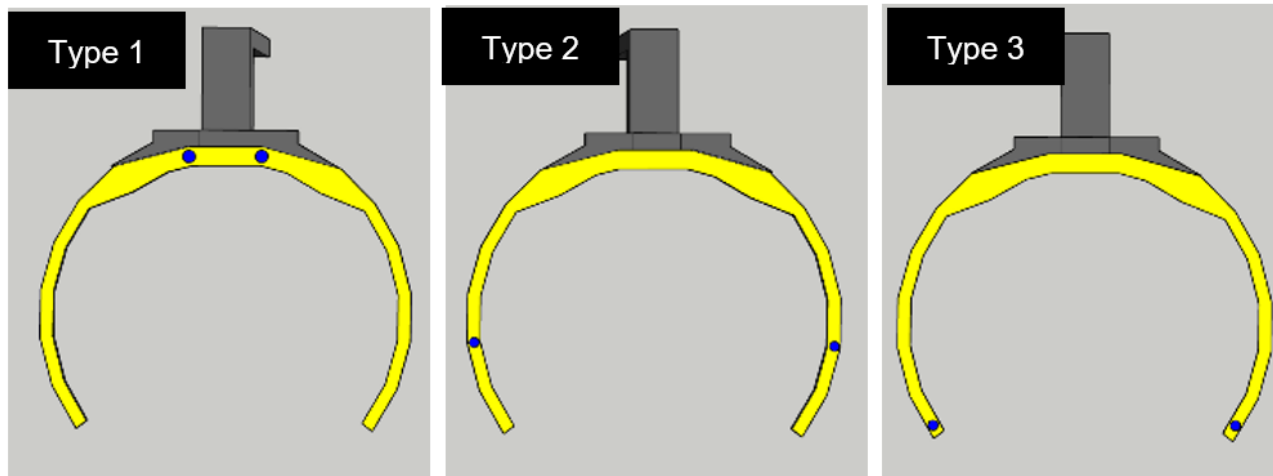
Test Set-up



On-pins:

The pins will be positioned in **three different diameters** arranged both ***symmetrical*** (equal distance between each other) and ***asymmetrical*** (two bottom pins are closer)

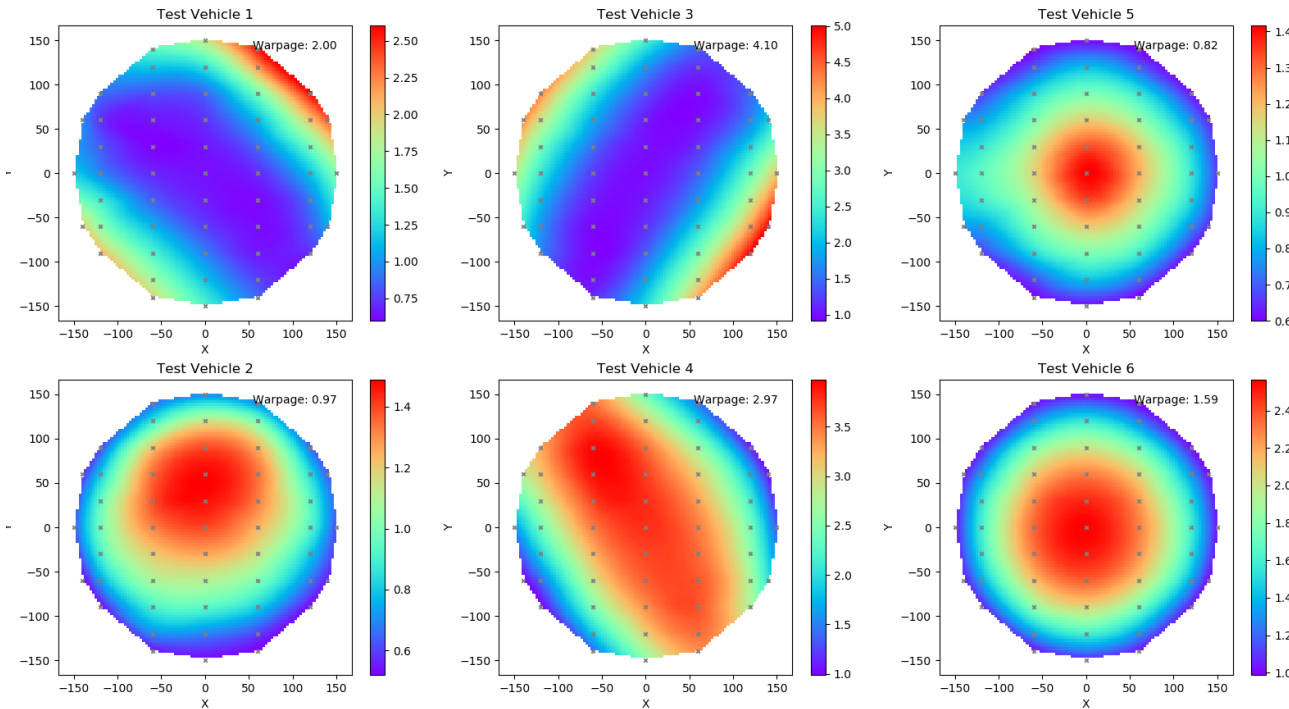
Test Set-up and Motivation



On- end effector:

The suction cups will be placed in three different positions; base , middle and tip which corresponds to Type 1, 2, and 3 respectively.

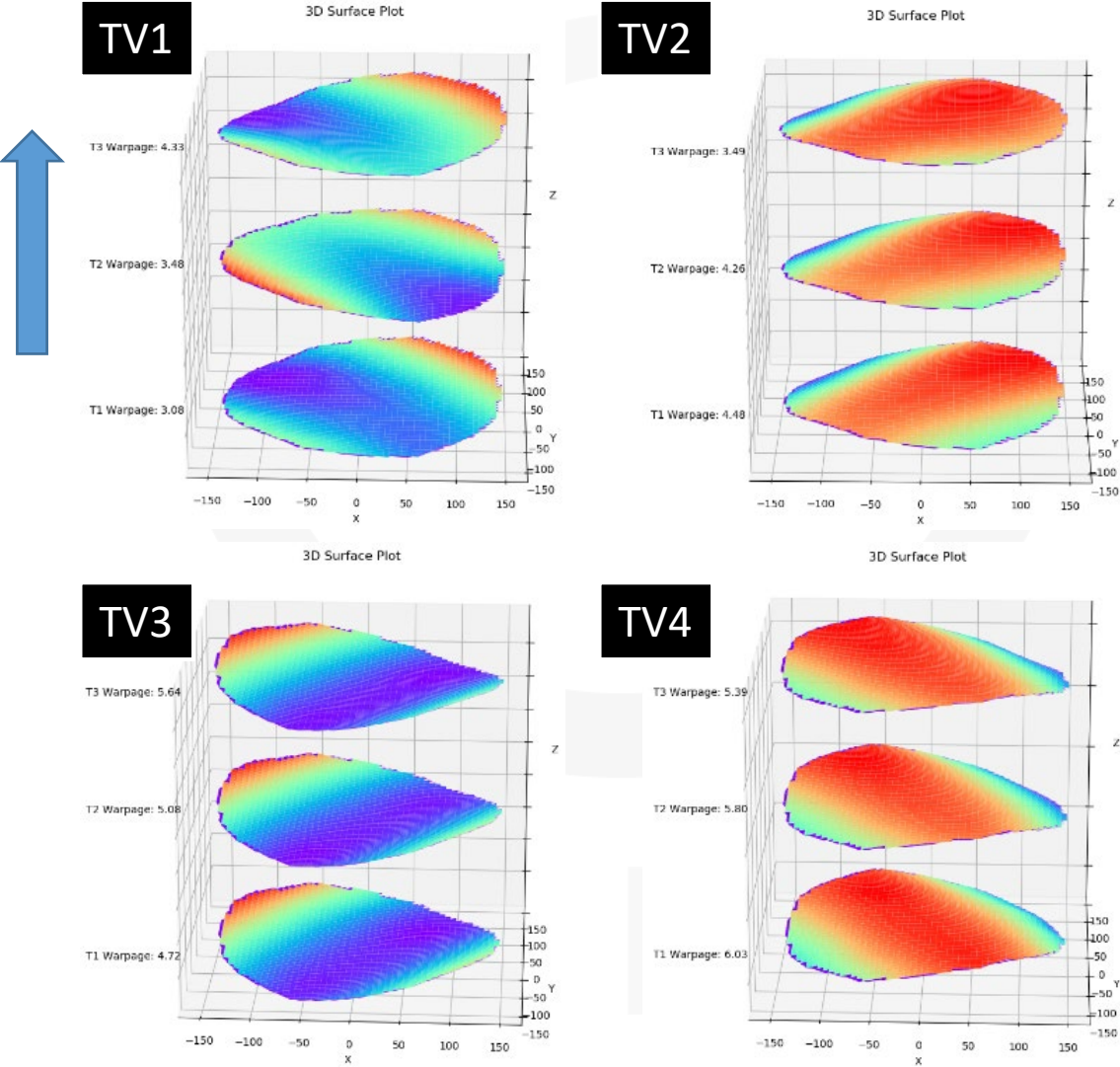
Test Vehicles



TV	Thickness	Shape	Mold Volume	Warpage
1	0.45mm	Smile	>80%	2.00mm
2	0.45mm	Frown/ Concave	>80%	0.97mm
3	0.90mm	Smile	>80%	4.10mm
4	0.90mm	Frown	>80%	2.97mm
5	0.55mm	Concave	>60%	0.82mm
6	0.90mm	Concave	>60%	1.59mm

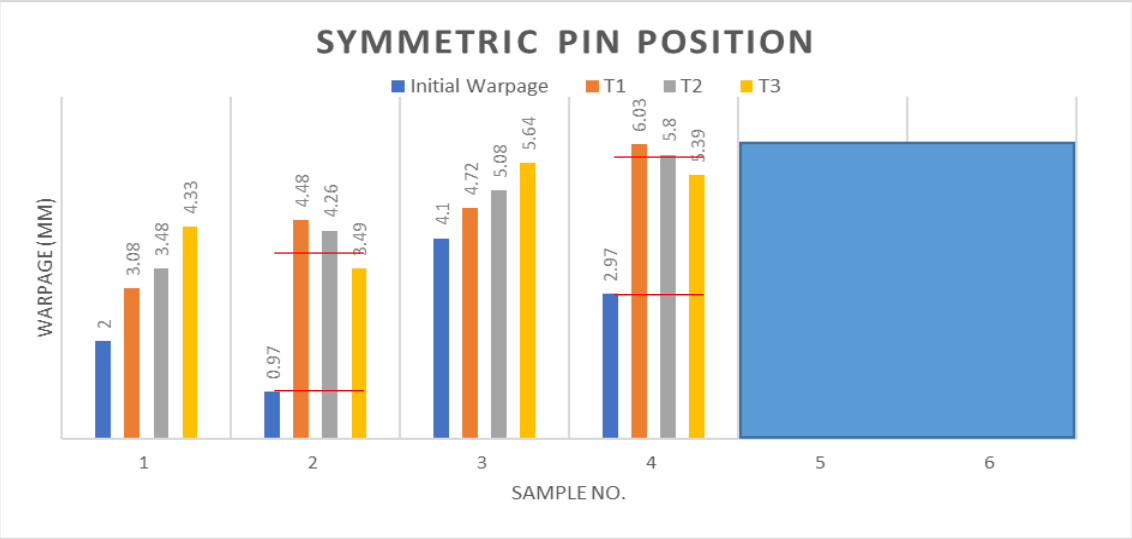
Note: All samples uses one type of mold compound, different material may have different result.
The wafers are tested post debonding process.

Warpage Response: On-Pins



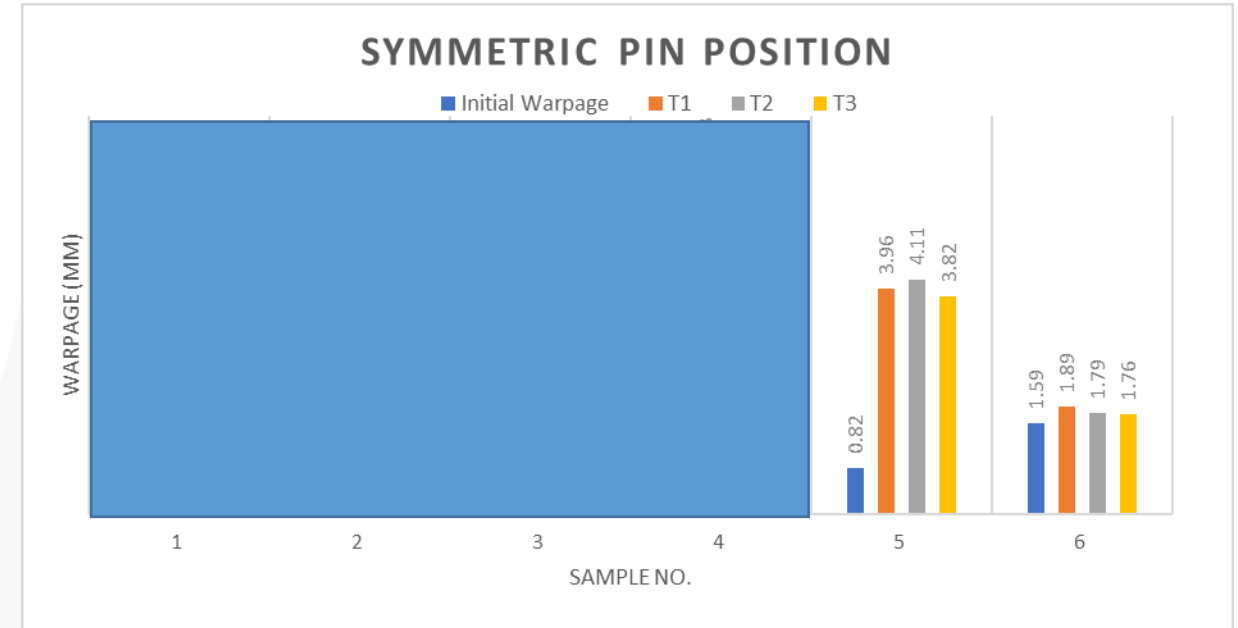
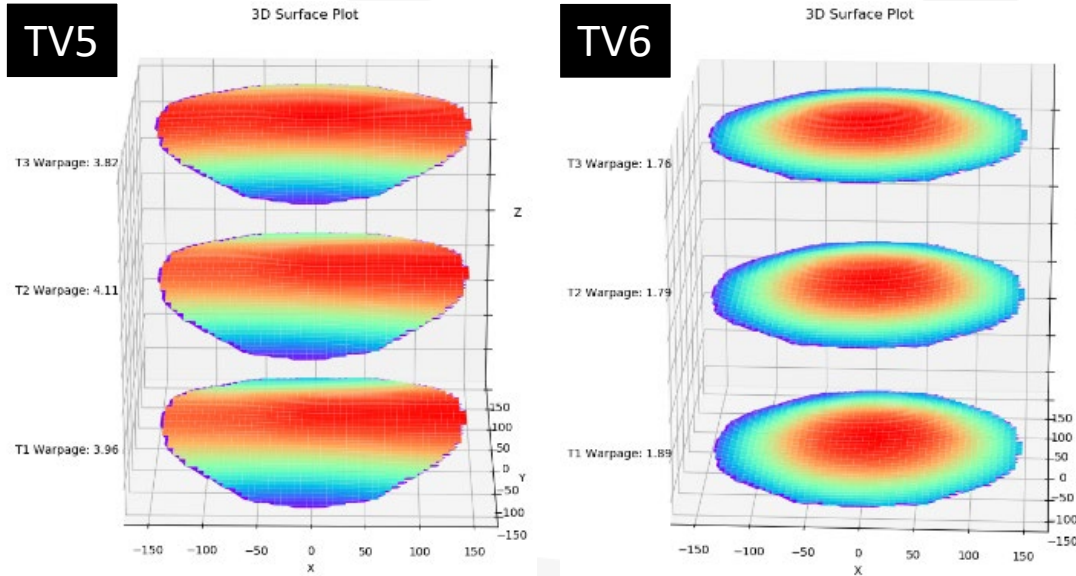
Symmetric Pin Placement

Sample		1	2	3	4
Initial Warpage		2.00	0.97	4.10	2.97
Symmetric	T3	4.33	3.49	5.64	5.39
	T2	3.48	4.26	5.08	5.80
	T1	3.08	4.48	4.72	6.03

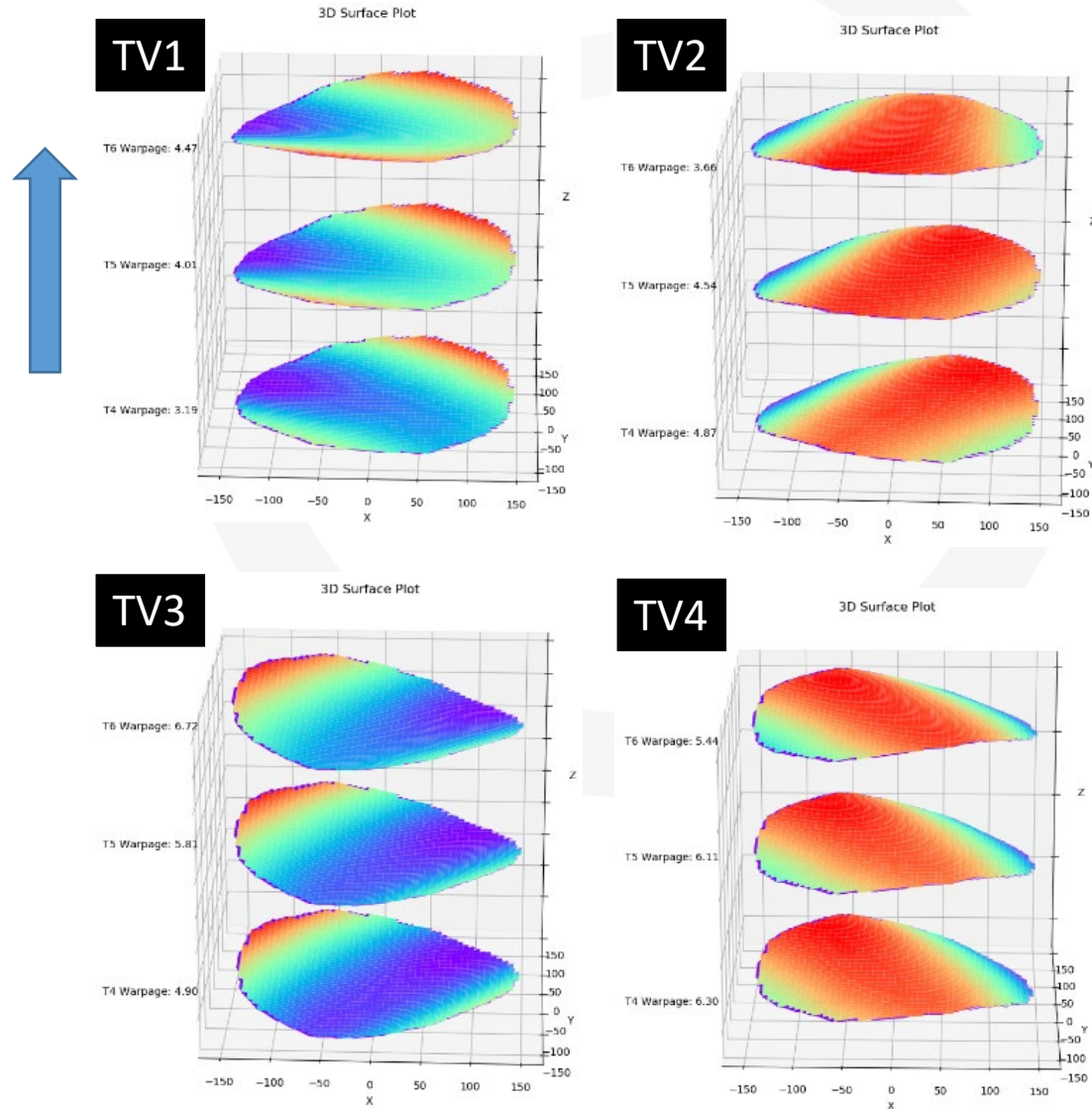


Warpage Response: On-Pins

Symmetric Pin Placement

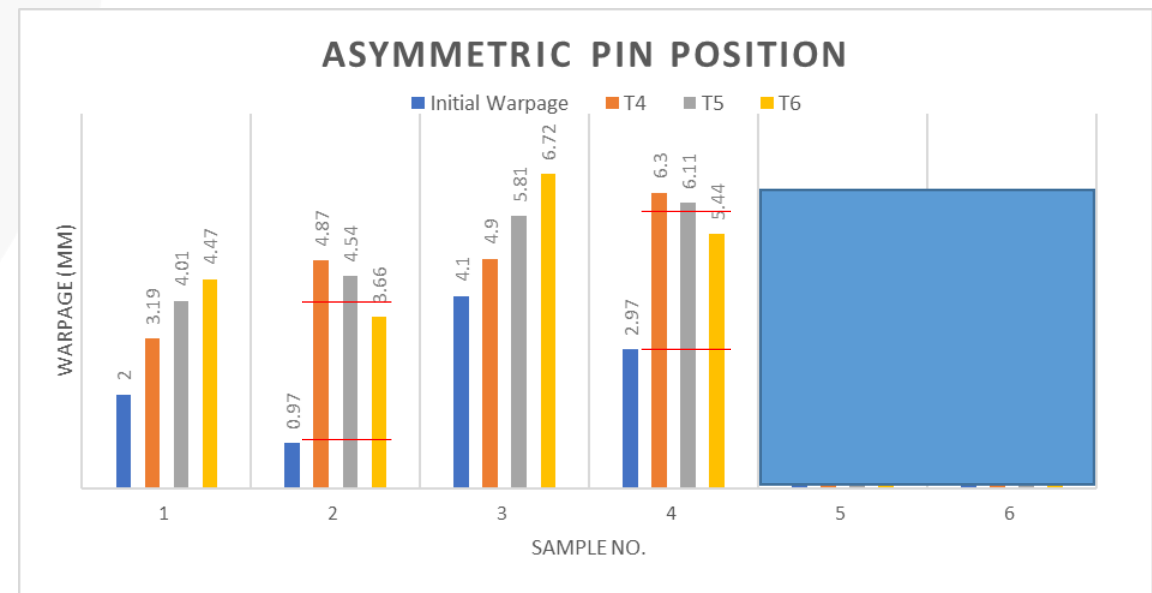


Warpage Response: On-Pins



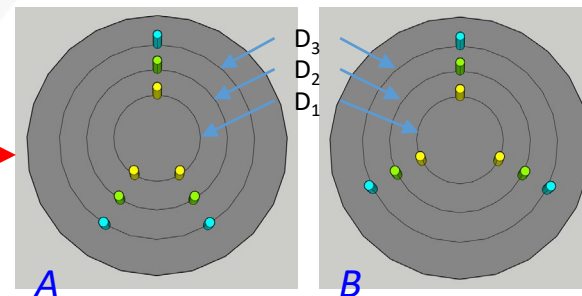
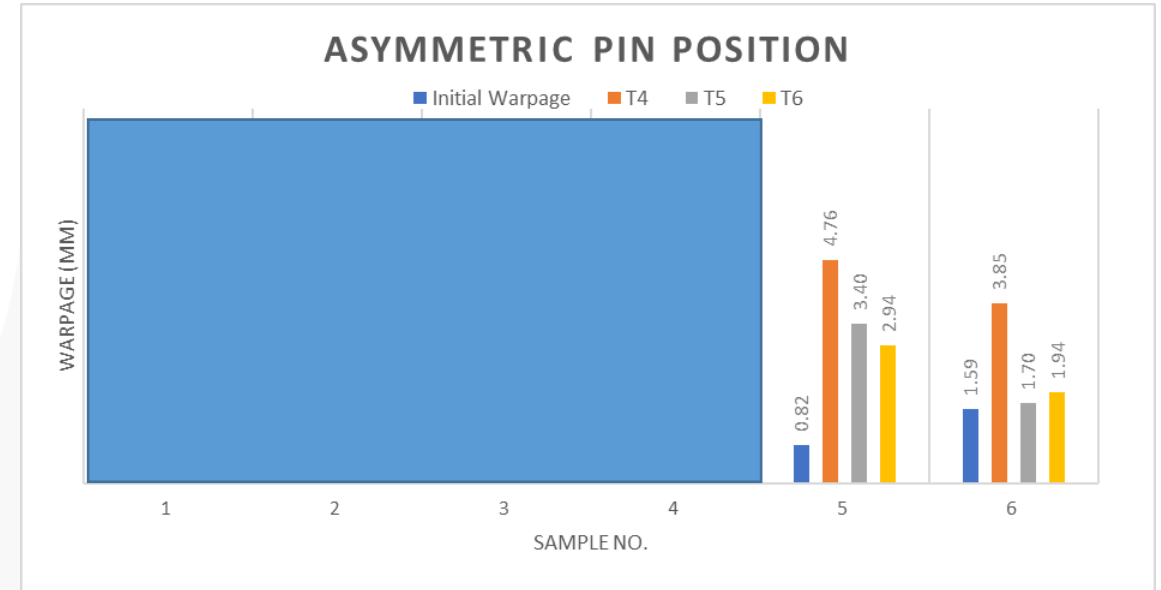
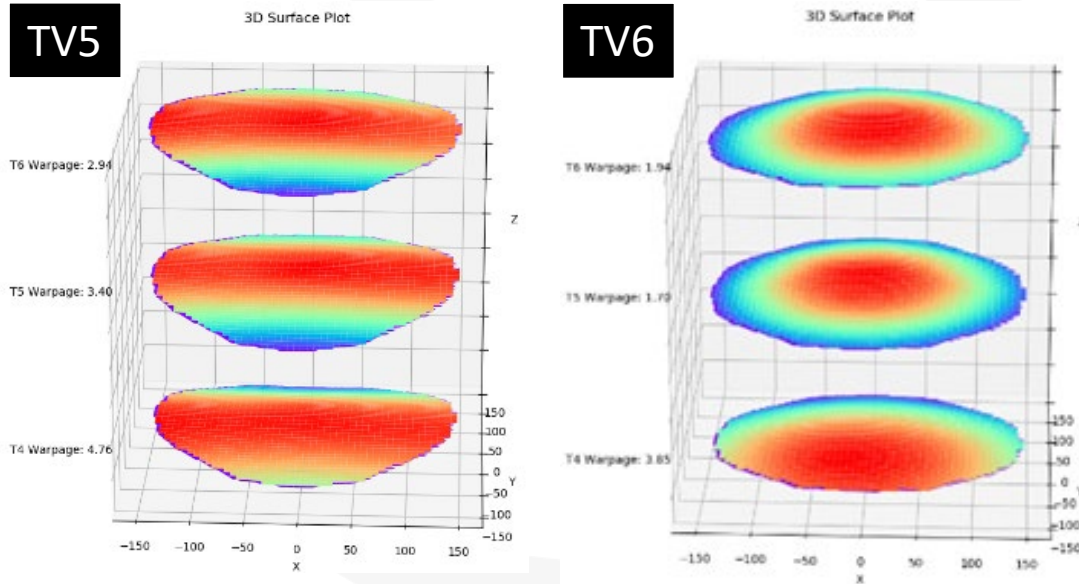
Asymmetric Pin Placement

Sample		1	2	3	4
Initial Warpage		2.00	0.97	4.10	2.97
Asymmetric	T6	4.47	3.66	6.72	5.44
	T5	4.01	4.54	5.81	6.11
	T4	3.19	4.87	4.9	6.3

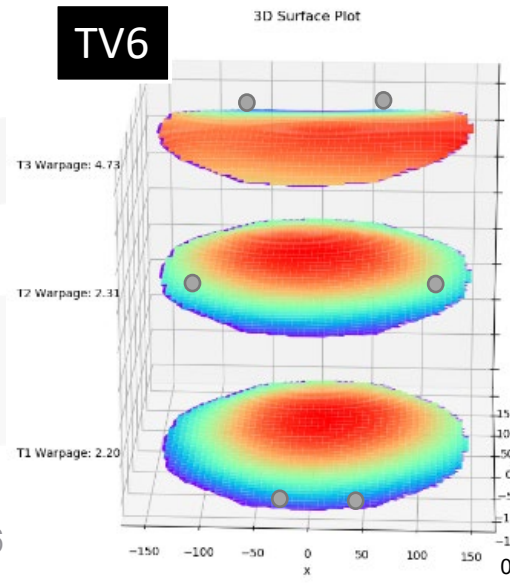
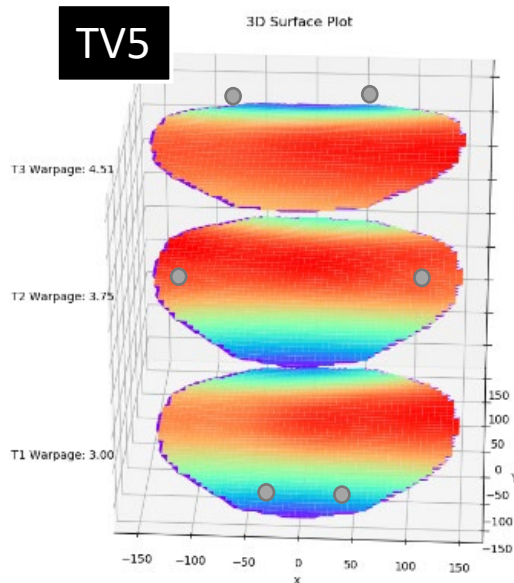
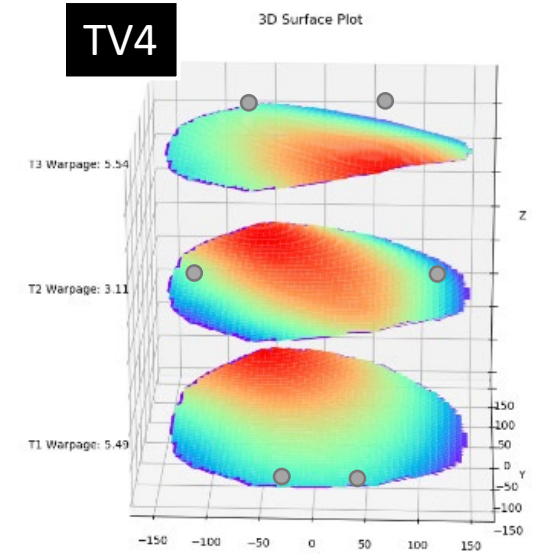
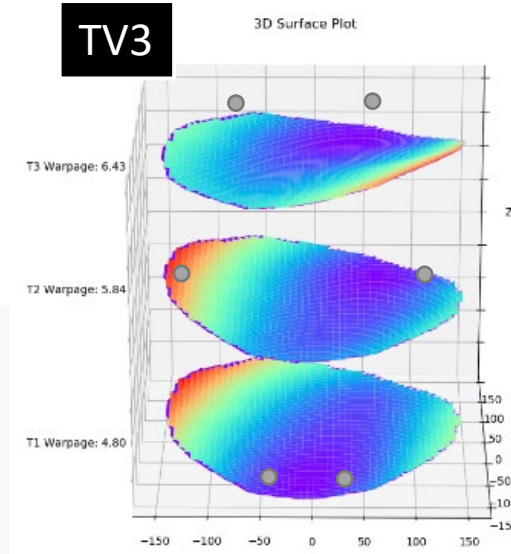
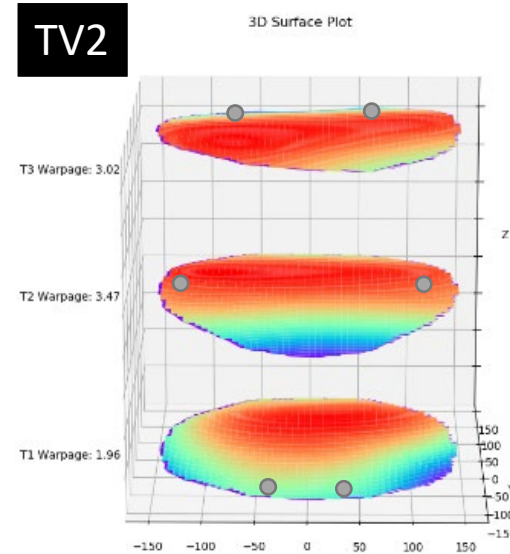
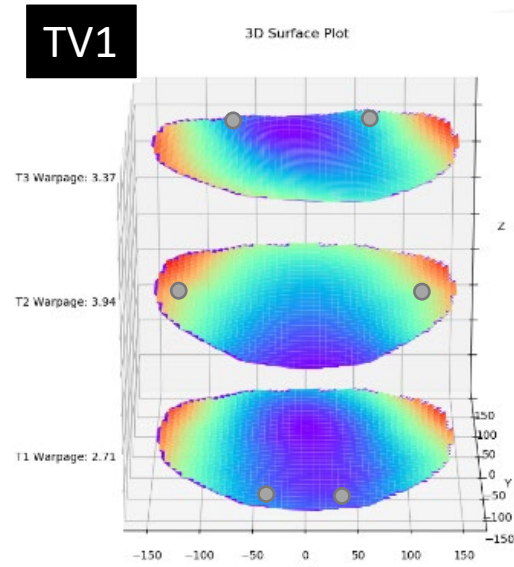


Warpage Response: On-Pins

Asymmetric Pin Placement



Warpage Response: On-End Effector



TV	Initial Warpage	Type 1	Type 2	Type 3
1	2.00mm	2.71	3.94	3.37
2	0.97mm	1.96	3.47	3.02
3	4.10mm	4.80	5.84	6.43
4	2.97mm	5.49	3.11	5.54
5	0.82mm	3.04	3.75	4.51
6	1.59mm	2.20	2.31	4.73

Observations and Conclusion

Addressing warpage issues in the production line can be expensive and time consuming. Changing the end-effector and pin positioning are some of the common ways to mitigate warpage effects in the production and enable high volume manufacturing.

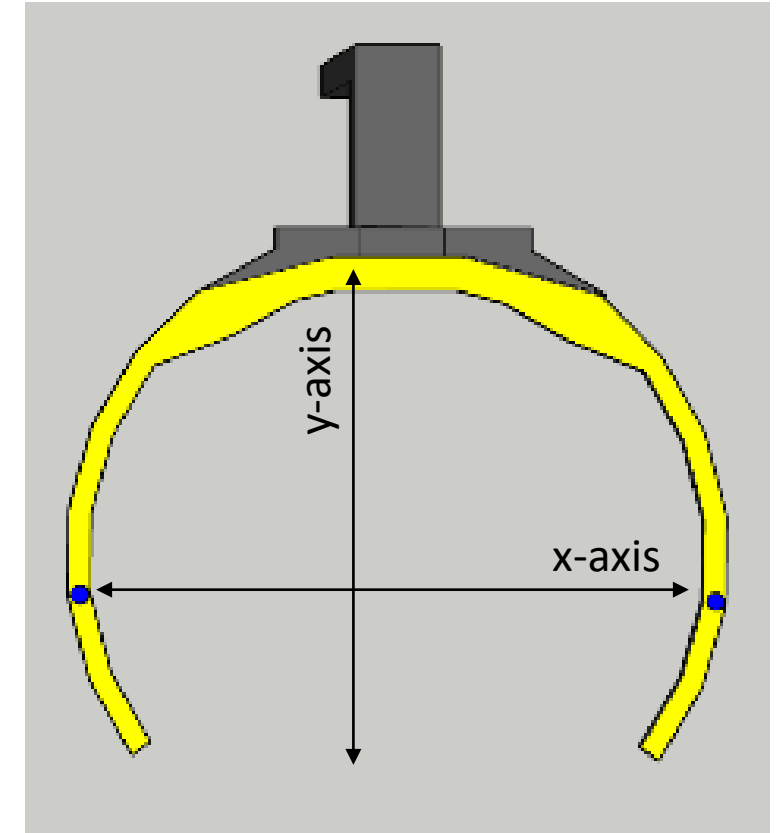
On pins:

- Pins cause warpage regardless of initial attributes.
 - Smiling wafers show increasing warpage with distance, frowning wafers show opposite, but have higher change (~3mm).
 - Lower mold density wafers hold shape better, no warpage change with pin distance.
- Asymmetric pin positions cause is assumed to cause weight imbalance and resulted to higher warpage.

Observations and Conclusion

On end-effector:

- Thin wafers show a slight correlation between increasing warpage with increasing suction cup distance on the x-axis.
- Thick wafers show no correlation and resist vacuum.
- Wafers with low mold density show increasing warpage with increasing suction cup distance from the base of the tip of the end effector on the y-axis.





Thank You!